

### Feature

- Precision MEMS process
- High performance, shielded, Micro-cavity structure
- Silicon substrate, 50Ω CPW output
- Au wire bonding, for MCM applications

### Environmental Specifications

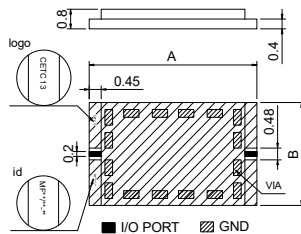
Operating Temperature	-55°C~+85°C
Storage Temperature	-55°C~+125°C
Max. Input Power	35dBm

### Electrical Specifications(T<sub>A</sub>=+25°C)

Parameter	Min.	Typ.	Max.	Unit
Center Freq. (f <sub>0</sub> )	-	11.65	-	GHz
Pass Band	11.6	-	13.1	GHz
Ripple in Pass band	-	-	1	dB
Insertion Loss @ f <sub>0</sub>	-	-	2.5	dB
Return Loss	12	-	-	dB
Out of band Attenuation	≥ 20@10.9GHz&13.75GHz			dB
	≥ 30@10.7GHz&13.85GHz			dB
	≥ 60@DC~10GHz			dB
Group Delay Variation	≤ 0.5@11.6~13.1GHz			ns
Linear Phase	≤ ±13@11.6~13.1GHz			°

S2P file name: SiMF12R5\_R7-8D3.s2p

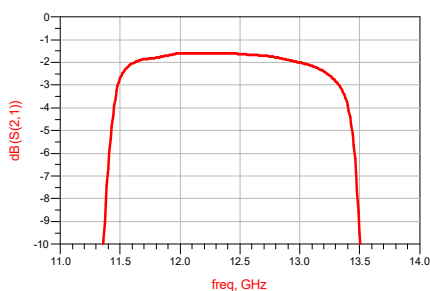
### Outline Drawing



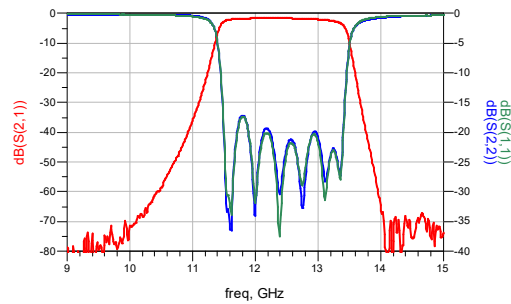
Symbol	Value (mm)		
	Min.	Nominal	Max.
A	7.9	-	8.0
B	2.9	-	3.0

### Typical Test Curves

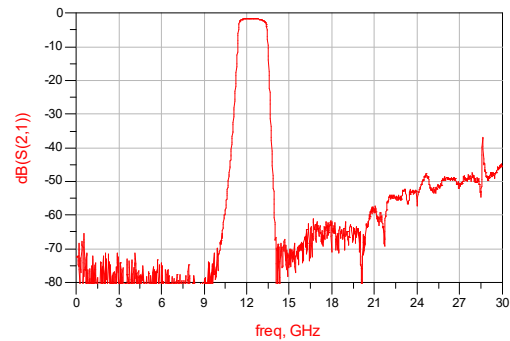
Insertion Loss VS Frequency (T<sub>A</sub>=25°C)



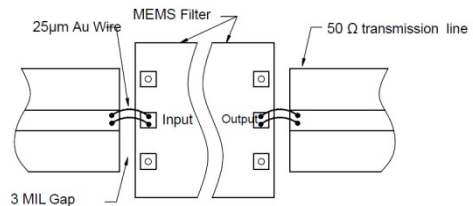
Insertion Loss & Return Loss VS Frequency (T<sub>A</sub>=25°C)



Broadband Insertion Loss VS Frequency (T<sub>A</sub>=25°C)



### Recommended Assembly Diagrams



### Application Notes:

1. The chip is back-metalized and can be die mounted with AuSn eutectic performs or with electrically conductive epoxy (for example ME8456).
2. The die should be assembled on carriers like Kovar or Mu-Cu which have same Coefficient of thermal expansion. (2.9ppm/°C) with Silicon, thickness 0.2mm max.
3. Handle the chips in a clean environment. DO NOT attempt to clean the chip using liquid cleaning systems.
4. Handle the chip along the edges with a vacuum collet or with a sharp pair of bent tweezers.
5. Recommended to use T structure as below for bonding.



6. If you have any questions, please contact us.